

Anisotropic Etching of $\text{TiO}_2(110)$ Single-Crystal Surface with Aniline Solution Immersion for Step Direction Control

(¹Graduate School of Humanities and Sciences, Ochanomizu University, ²Graduate School of Science and Technology, Kumamoto University, ³Institute of Industrial Nanomaterials, Kumamoto University) ○Mami Takahari,¹ Taiga Goto,² Soichiro Yoshimoro,³ Toshihiro Kondo,¹

Keywords: Aniline (AN); $\text{TiO}_2(110)$ Single-Crystal Surface; Solution Immersion; Step direction control; Photocatalytic reaction

$\text{TiO}_2(110)$ single-crystal surface have been used as a model surface for photocatalytic reactions. It is important to control of a step direction on $\text{TiO}_2(110)$ surface because photocatalytic reactions depend on the step direction. However, there are few reports to control. In this study, we found $\text{TiO}_2(110)$ surface was etched and a uniform step structure in the $[001]$ direction formed after immersing of the clean $\text{TiO}_2(110)$ single-crystal substrate in an ethanol solution containing aniline.

It is known that AN is uniformly adsorbed on the $\text{TiO}_2(110)$ surface when it was vacuum deposited. However, AN was not adsorbed on the $\text{TiO}_2(110)$ surface from the solution. Nevertheless, its surface morphology was significantly different before and after the immersion into the ethanol solution containing AN (Fig. 1). Zigzag steps in the $[\bar{1}12]$ direction with many kinks were observed in the sample prepared by immersion into the solution without AN (sample Et), whereas linear $[001]$ direction steps were observed when the sample was immersed in the solution containing AN (sample AN). Since Ti was detected in the solution after immersion, it was concluded that the etching was promoted by the formation of TiO_2 -AN complex and its desorption as a result of adsorption of AN to step edged Ti.

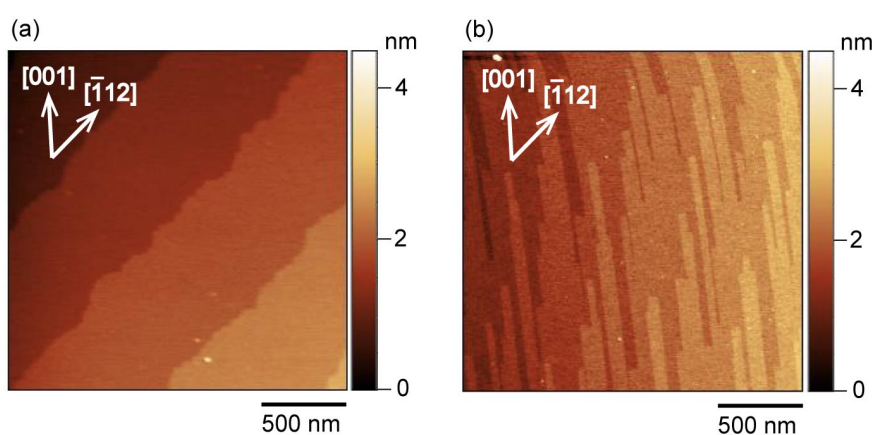


Figure 1 AFM images of (a) sample Et and (b) sample AN ($2\ \mu\text{m} \times 2\ \mu\text{m}$)¹⁾.

1) M. Takahari, T. Goto, S. Yoshimoto, T. Kondo, *Chem. Lett.* **2023**, 52, 823.